

Exhibit C

Excerpts from

LithoVision 2009, Lithography Technology Trends, S. Sivakumar

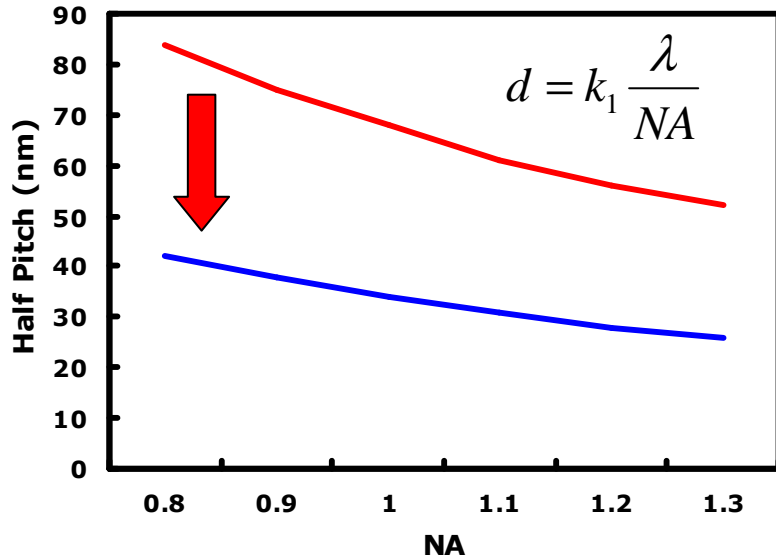
Litho**Vision** | 2009

Lithography Technology Trends



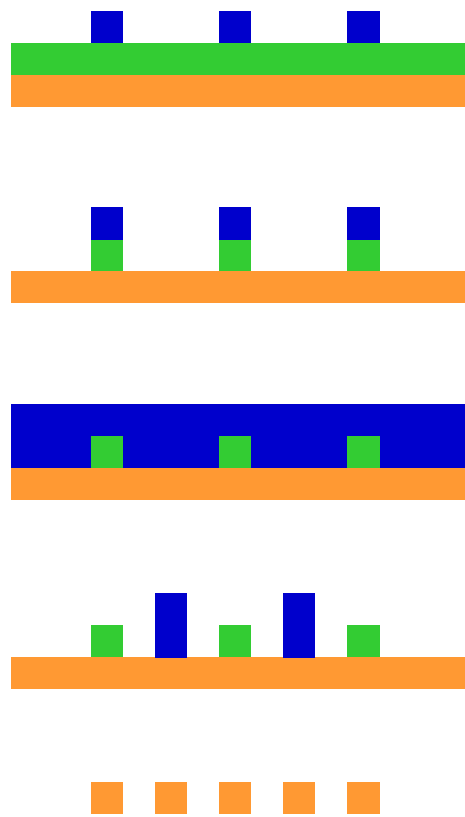
Sam Sivakumar
Intel Corporation

ArF Pitch Division (PD)

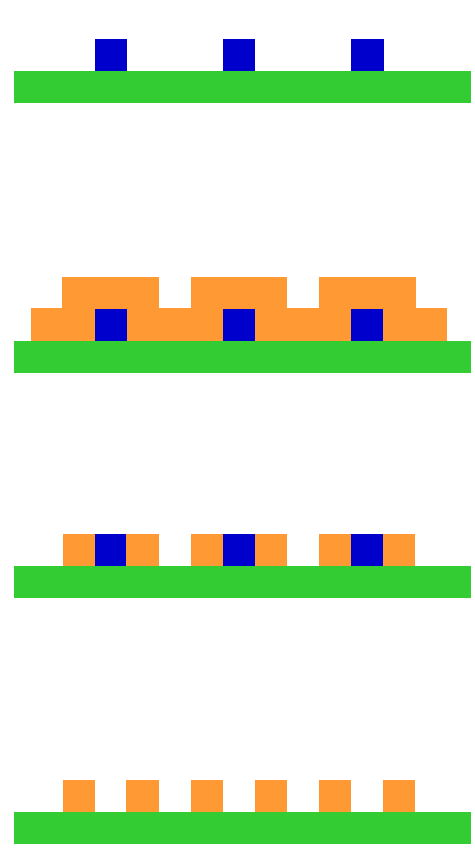


ArF PD gains significant resolution at the expense of process complexity

Double Patterning Pitch Division (DPPD)



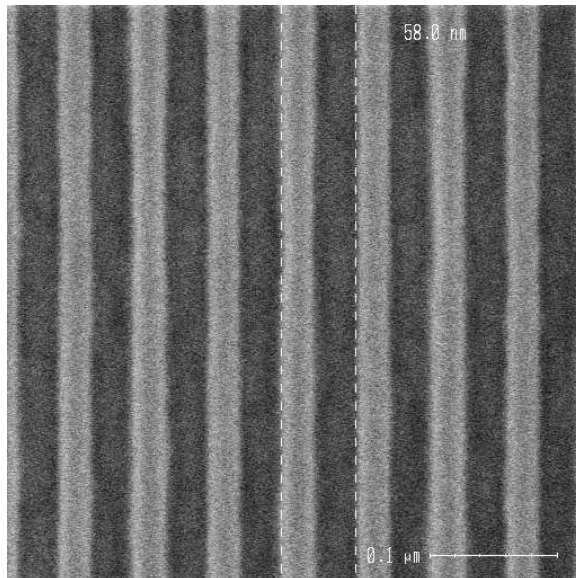
Spacer Based Pitch Division (SBPD)



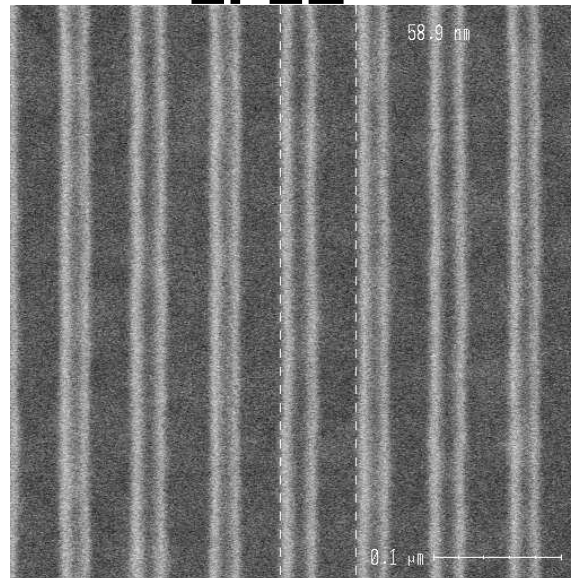
Double Patterning Pitch Division

- Most mature double patterning methods are either LELE (Litho/Etch/Litho/Etch) or LFLE (Litho/Freeze/Litho/Etch)
 - Line DP can be either. Space DP has to be LELE
- Key challenges are process complexity and synthesis issues in splitting original pattern into two masks

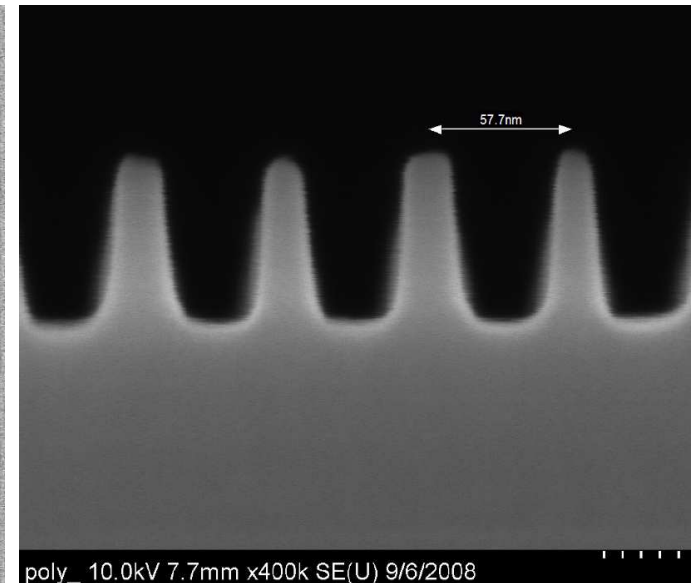
LFLE



Lithography - DP



Transfer to HM



Transfer to Substrate

